

#28  
1/22/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

|            |   |             |          |
|------------|---|-------------|----------|
|            | Sylvia H. Pas   | Examiner:   | TBD      |
| Serial No: | TBD   | Art Unit:   | TBD      |
| Filed:     | 01/11/01  | Docket No.: | TI-22398 |
| For:       | SYSTEM AND METHOD FOR INTEGRATED OXIDE REMOVAL AND<br>PROCESSING OF A SEMICONDUCTOR WAFER |             |          |

PRELIMINARY AMENDMENT

January 11, 2001

Assistant Commissioner for Patents

Washington, DC 20231

Dear Sir:

Please amend the above referenced application as follows:

In the Specification:

Page 1, before line 1, insert --☒ This application claims priority under 35 USC §

119(e)(1) of provisional application numbers **60/178,647** filed **01/28/00**.--